



X-ray photoelectron spectroscopy survey scans of 25W remote plasma treated 45 wt.% POSS-MA thin films. Samples were as-deposited (no plasma), 100 s 100 sccm N₂ plasma, 40 s 5:95 sccm O₂: N₂ plasma, and 100 s 5:95 sccm O₂: N₂ plasma.